

Applicant: Kei-Yu Ko
 Serial No.: 08/846,671
 Filing Date: April 30, 1997
 For: UNDOPED SILICON DIOXIDE AS AN ETCH STOP FOR SELECTIVE ETCH OF
 DOPED SILICON DIOXIDE

Att'y DocketNo. 11675.114

70595

JUL 22 1997

INFORMATION DISCLOSURE CITATIONS MADE BY APPLICANTU.S. Patent Documents

<u>Examiner Initial*</u>	<u>Patent Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Sub Class</u>	<u>Filing Date</u>
O A1	5,286,344	2/15/94	Blalock et al.	156	657	6/15/92
A2	5,366,590	11/22/94	Kadomura	156	662	3/17/94
O A3	5,423,945	6/13/95	Marks et al.	156	662.1	9/8/92
A4						
A5						

Foreign Patent Documents

<u>Examiner Initial*</u>	<u>Document Number</u>	<u>Publ. Date</u>	<u>Country or Patent Office</u>	<u>Sub Class</u>	<u>Class</u>	<u>Trans-lation</u>
A6						
A7						

Other Documents

(including author (if listed), title, relevant pages, date of publication including at least month and year).

Examiner
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A8

Examiner: George Goudreau Date Considered: 2-2-001

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITIGATION (Use several sheets if necessary)			Docket Number (Optional) 11675.114	Application Number 08/846,671		
			Applicant(s) Kei-Yu Ko			
			Filing Date April 30, 1997	Group Art Unit 1765		
U.S. PATENT DOCUMENTS						
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS
GAY	1	5,677,227	10/14/97	Yang, et al.	437	60
GAY	2	5,626,716	5/6/97	Bosch, et al.	438	723
FOREIGN PATENT DOCUMENTS						
REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation <input type="checkbox"/> YES <input checked="" type="checkbox"/> NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
EXAMINER George Goudreau			DATE CONSIDERED 1-99			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						

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